

C1
10. (Twice Amended) A photosensitive resin composition for i-line stepper using monochromatic light, which comprises (1) a polyimide precursor, formed from an oxydiphthalic acid or acid anhydride thereof as a reactant, a 20 μ m film thickness of said polyimide precursor having a transmittance, at 365 nm, of at least 40%; (2) an addition-polymerizable compound; and (3) a photoinitiator.

C2
21. (Amended) A photosensitive resin composition according to claim 10, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.

C3
Sale
201
25. (Amended) A photosensitive resin composition which comprises (1) a polyimide precursor formed from an oxydiphthalic acid or acid anhydride thereof with a diamine, (2) an addition-polymerizable compound, and (3) a photoinitiator, and which is adapted to be exposed and developed using an i-line stepper which uses monochromatic light.

C4
28. (Amended) A photosensitive resin composition according to claim 25, wherein the addition-polymerizable compound is tetraethylene glycol dimethacrylate.